

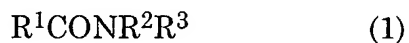
WHAT IS CLAIMED IS:

1. A resist stripping composition comprising 0.001 to 0.5% by weight of a fluorine compound, a mixed solvent of an amide solvent and an ether solvent and water.
- 5 2. The resist stripping composition according to Claim 1, wherein the fluorine compound is a fluoride of ammonium, amine or quaternary organic ammonium.
3. The resist stripping composition according to Claim 1, wherein the ether solvent is a glycol ether.
- 10 4. The resist stripping composition according to Claim 1, wherein the amide solvent has a dielectric constant of 25 or more.
5. The resist stripping composition according to Claim 1, wherein the fluorine compound is selected from the group consisting of hydrogen fluoride, ammonium fluoride, acid ammonium fluoride, methylamine hydrogen fluoride, 15 ethylamine hydrogen fluoride, propylamine hydrogen fluoride, tetramethylammonium fluoride, tetraethylammonium fluoride, ethanolamine hydrogen fluoride, methylethanolamine hydrogen fluoride, dimethylethanolamine hydrogen fluoride, hydroxylamine hydrogen fluoride, dimethylhydroxylamine hydrogen fluoride, and triethylenediamine hydrogen 20 fluoride.
6. The resist stripping composition according to Claim 1, wherein the fluorine compound is ammonium fluoride.
7. The resist stripping composition according to Claim 1, further comprising a corrosion inhibitor.
- 25 8. The resist stripping composition according to Claim 6, wherein the corrosion inhibitor is at least one compound selected from the group consisting of aromatic hydroxy compounds, carboxylic compounds, organic salts of the carboxylic compounds and chelating compounds.
9. The resist stripping composition according to Claim 1, wherein the

amide solvent is at least one compound selected from the group consisting of formamide, N-methylformamide, N,N-dimethylformamide, acetamide, N-methylacetamide, N,N-dimethylacetamide, N,N-dimethylpropanamide, lactamide, hydroxybutyramide, dimethyl sulfoxide, sulfolane, hexamethyl phosphoramidate, pyrrolidone, N-methylpyrrolidone, tetramethylurea, N,N'-dimethylethyleneurea, N, N'-dimethylpropyleneurea, methyl dimethylcarbamate, and acetonitrile.

10. The resist stripping composition according to Claim 1, wherein the ether compound is at least one compound selected from the group consisting of methyl cellosolve, ethyl cellosolve, butyl cellosolve, dimethoxyethylene, diethylene glycol monomethyl ether, diethylene glycol monobutyl ether, diethylene glycol monoethyl ether, diethylene glycoldimethyl ether, triethylene glycol monomethyl ether, triethylene glycol monobutyl ether, polyethylene glycol monomethyl ether, methoxybutanol, methoxymethylbutanol, dioxane, dioxolane, trioxane, tetrahydrofuran, crown ether, propylene glycol monomethyl ether, dipropylene glycol monomethyl ether, tripropylene glycol monomethyl ether, propylene glycol monobutyl ether, dipropylene glycol monobutyl ether, tripropylene glycol monobutyl ether, polyethylene glycol and polypropylene glycol.

11. The resist stripping composition according to Claim 1, wherein the amide compound is represented by the following formula 1:



wherein R^1 , R^2 and R^3 are each independently hydrogen, alkyl group or hydroxyalkyl group.

12. The resist stripping composition according to Claim 1, wherein the ether compound is represented by the following formula 2:



wherein R^4 and R^5 are each independently alkyl group, alkoxyalkyl group, hydroxyalkyl group or hydroxyalkoxyalkyl group.

13. The resist stripping composition according to Claim 1, wherein the content of the amide solvent is 0.5% by weight or more and the content of the ether solvent is 0.5% by weight or more, each based on a total weight of the resist stripping composition.

5 14. The resist stripping composition according to Claim 1, wherein the content of the amide solvent is 0.5% by weight or more, the content of the ether solvent is 0.5% by weight or more, and the content of the mixed solvent is 30% by weight or more, each based on the total weight of the resist stripping composition.

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